

Fig. 1

Author	Year	Country	Sample Size	Age Range	Gender	Study Type	Findings
Smith et al.	2001	USA	150	18-25	Male	Experimental	High levels of aggression in response to provocation.
Johnson et al.	2003	Canada	200	26-35	Female	Survey	Aggression levels decreased with age.
Lee et al.	2005	South Korea	120	19-28	Male	Experimental	Aggression increased with alcohol consumption.
Wang et al.	2007	China	180	20-30	Male	Survey	Aggression levels were higher in urban areas.
Miller et al.	2009	USA	160	17-24	Male	Experimental	Aggression levels were higher in response to negative feedback.
Chen et al.	2011	Taiwan	140	21-30	Male	Survey	Aggression levels were higher in response to stress.
Ng et al.	2013	Malaysia	130	18-27	Male	Experimental	Aggression levels were higher in response to provocation.
Patel et al.	2015	India	110	22-31	Male	Survey	Aggression levels were higher in response to stress.
Kim et al.	2017	South Korea	100	19-29	Male	Experimental	Aggression levels were higher in response to provocation.
Yamamoto et al.	2019	Japan	90	20-30	Male	Survey	Aggression levels were higher in response to stress.

Fig. 2a

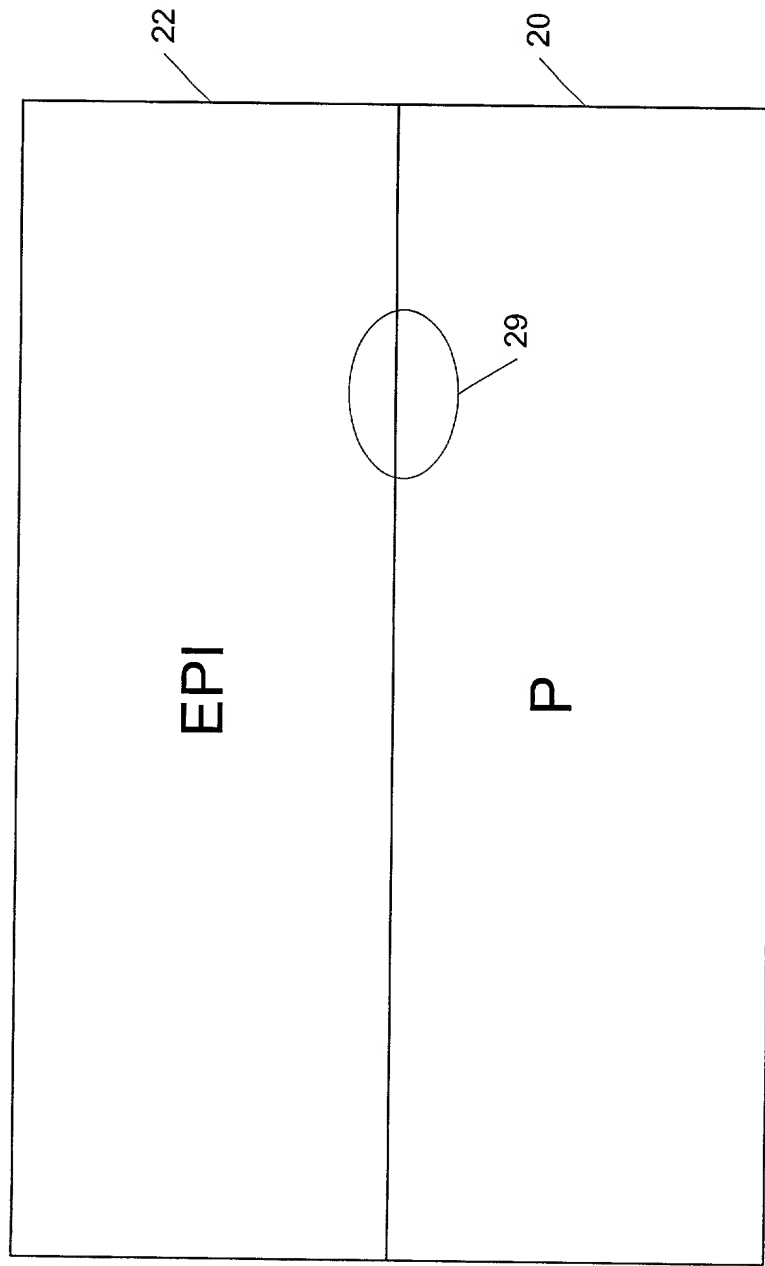


Fig. 2b

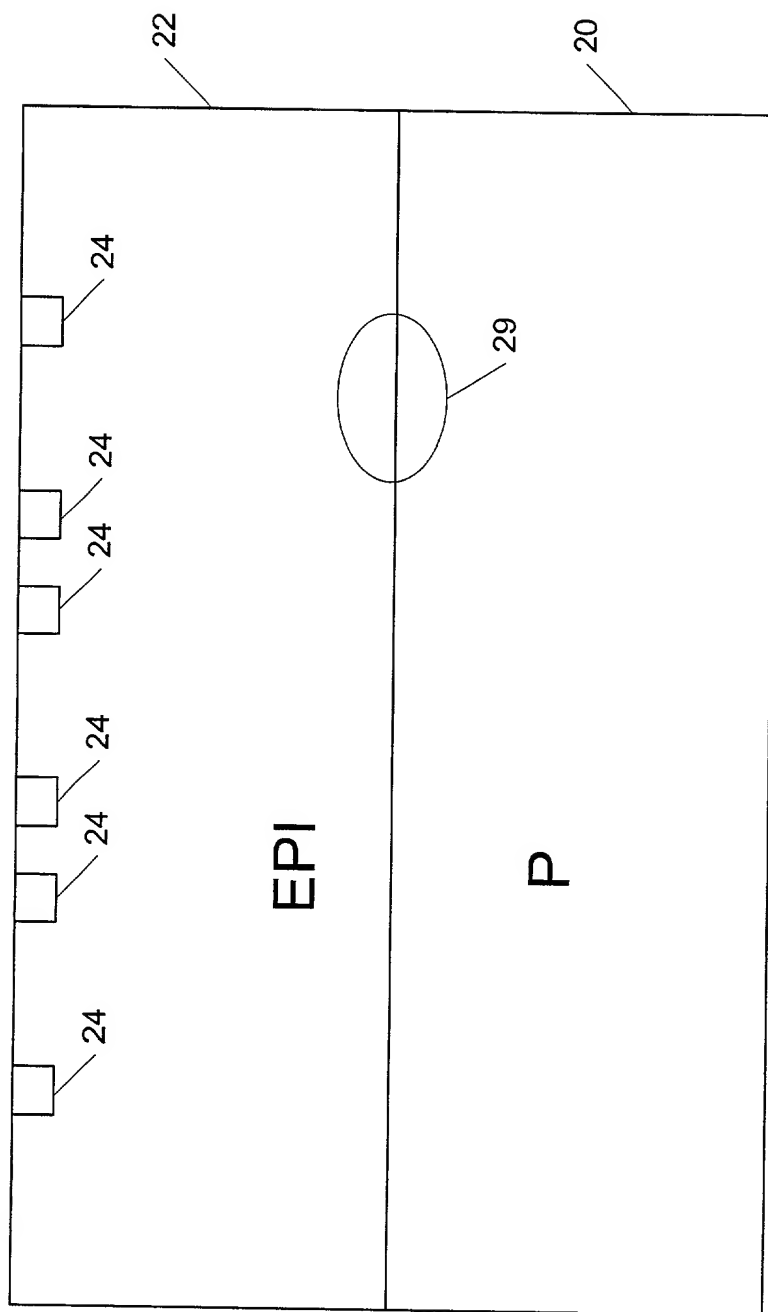


Fig. 2c

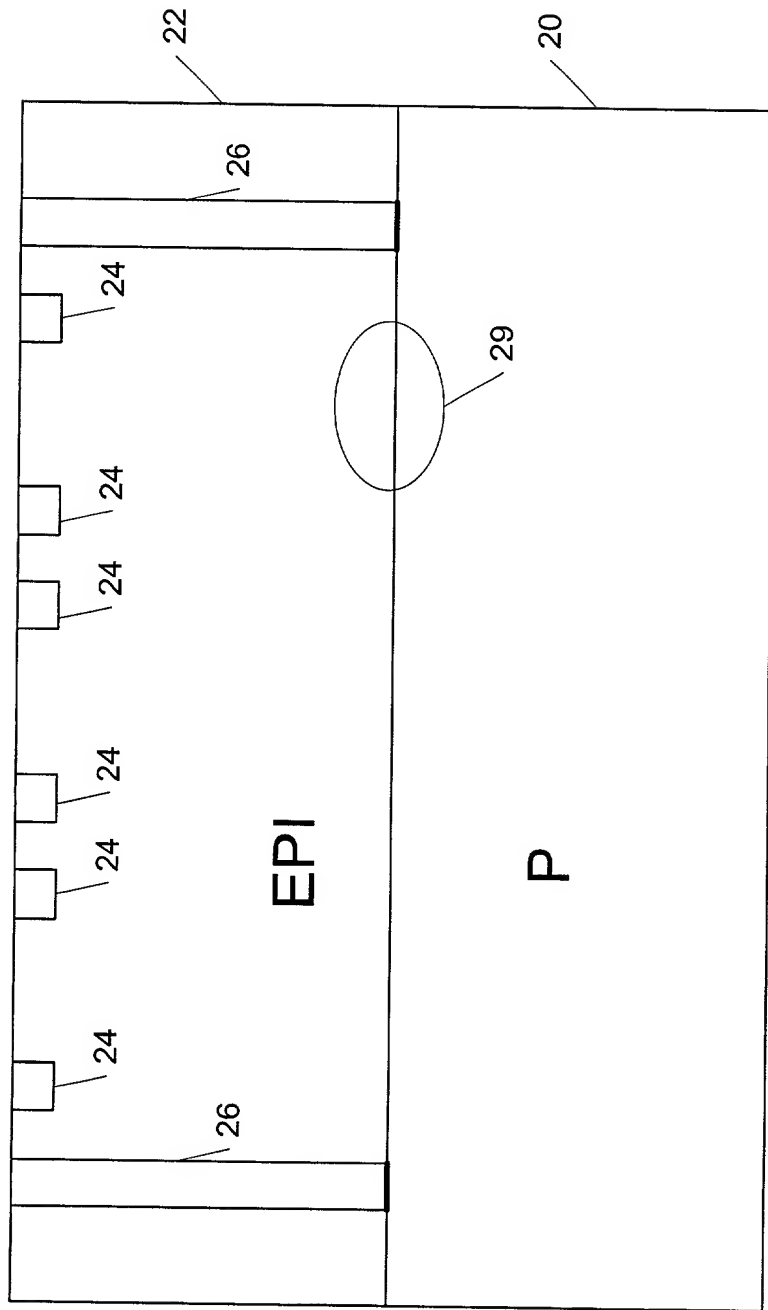


Fig. 2d

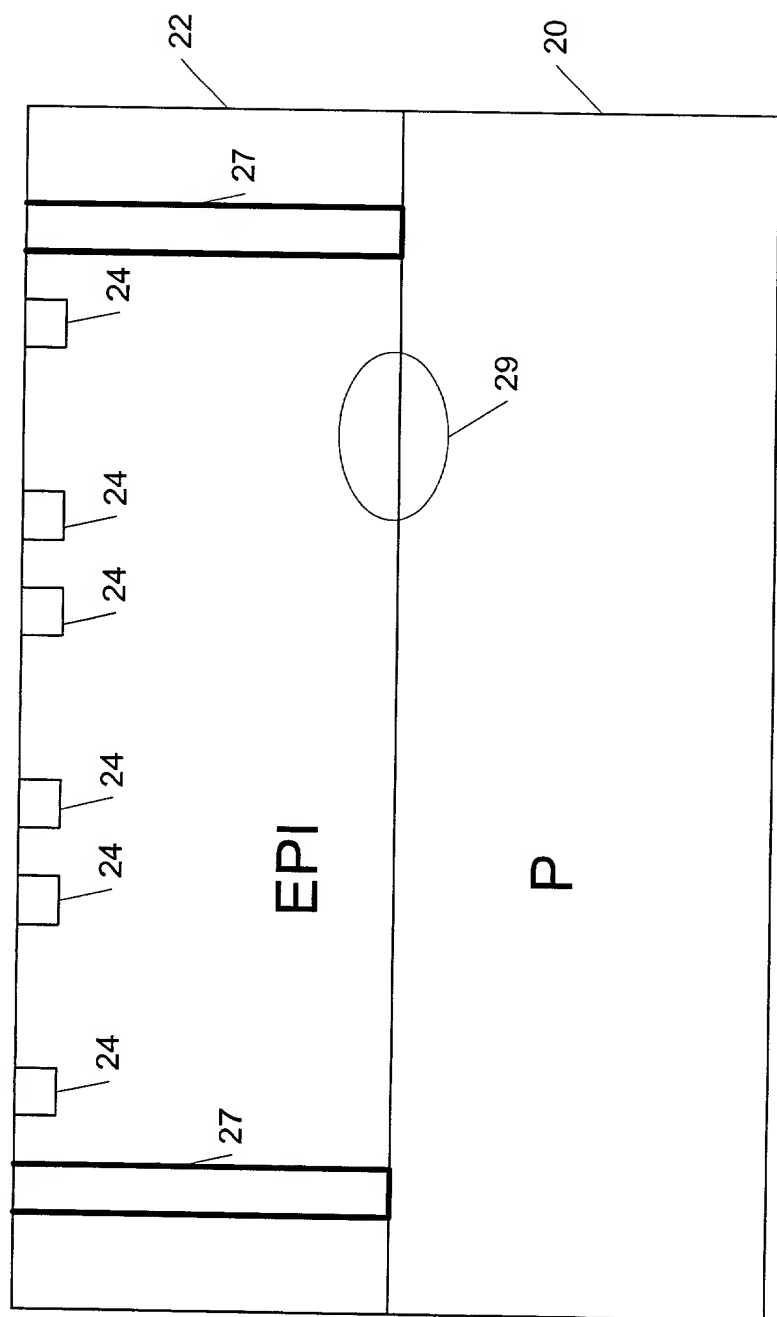


Fig. 2e

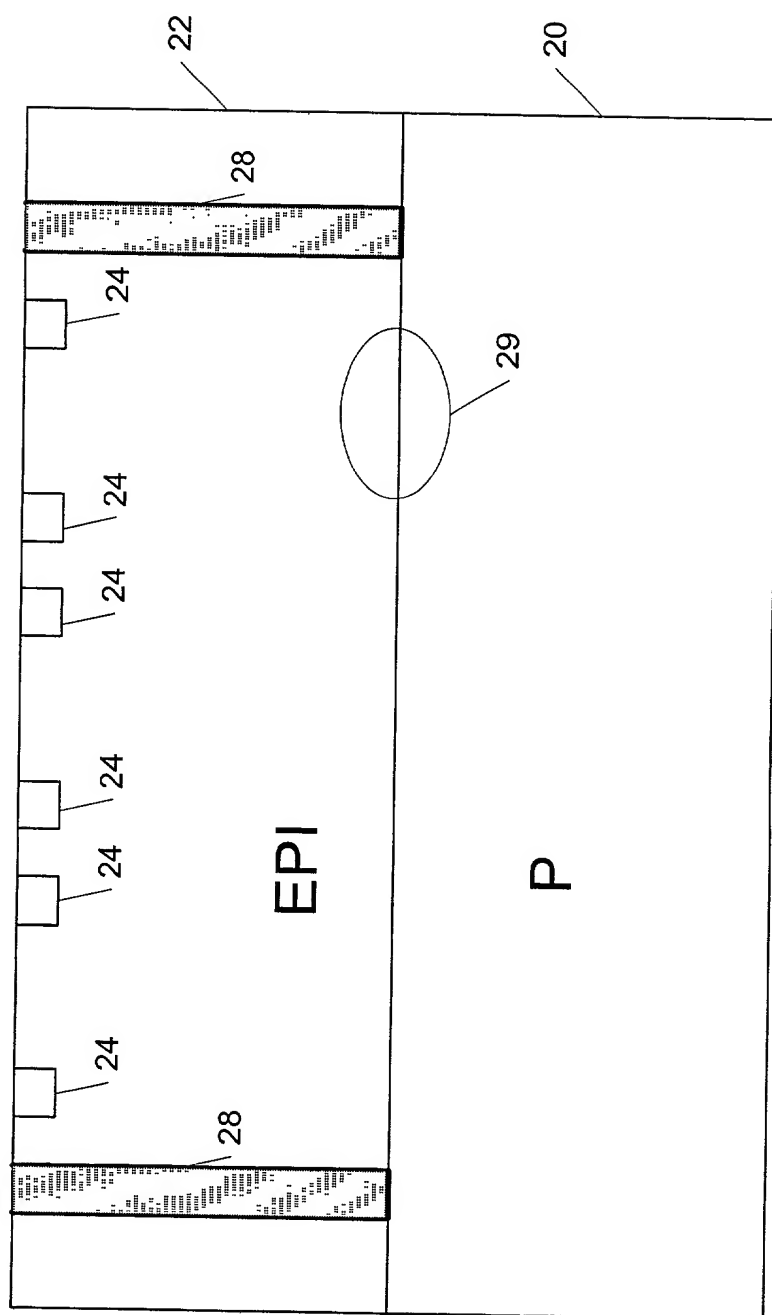


Fig. 2f

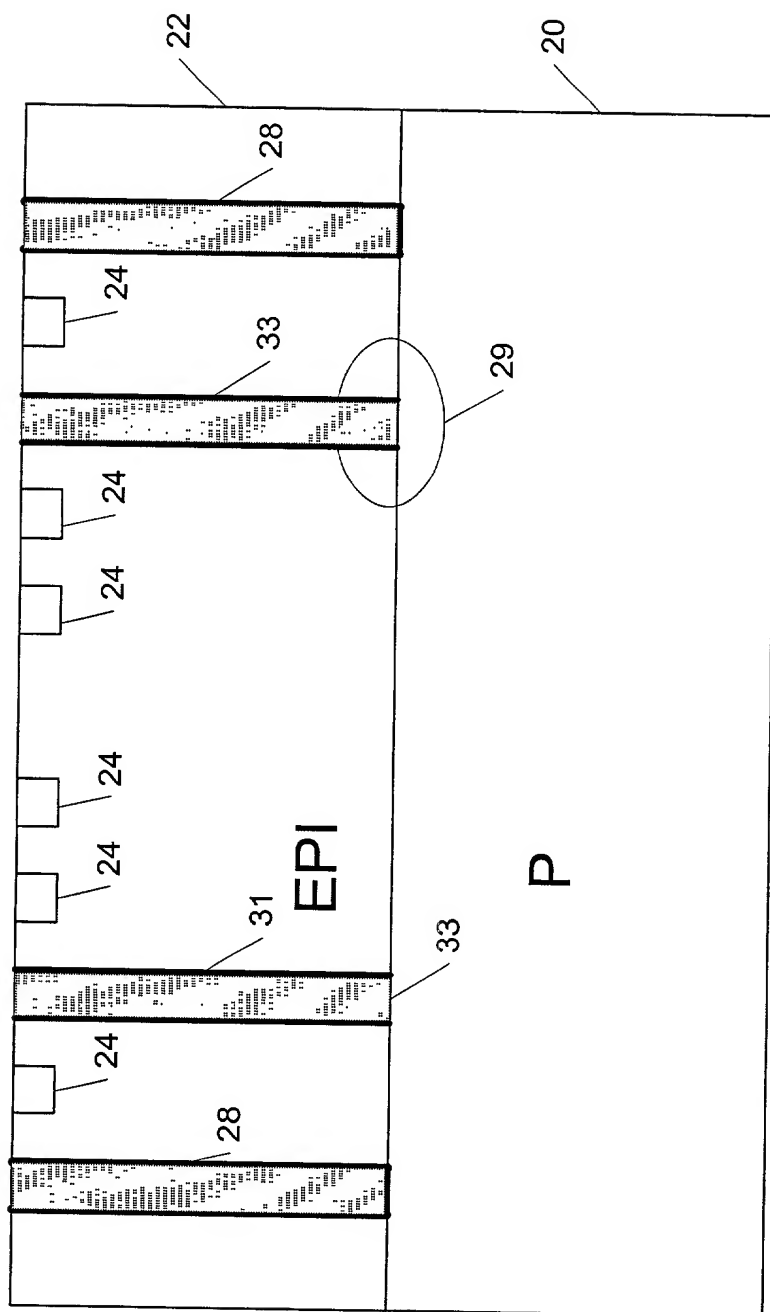


Fig. 29

⊗ L LENGTH
INTO
PAPER

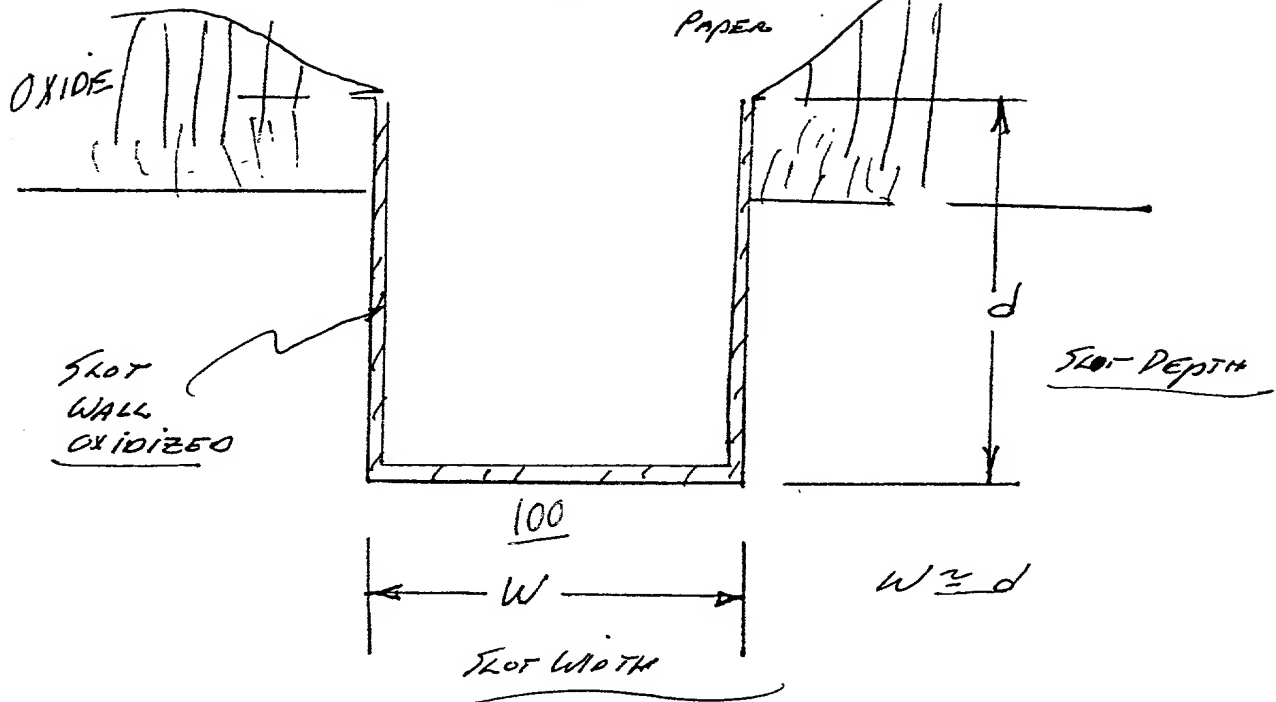


Fig. 3

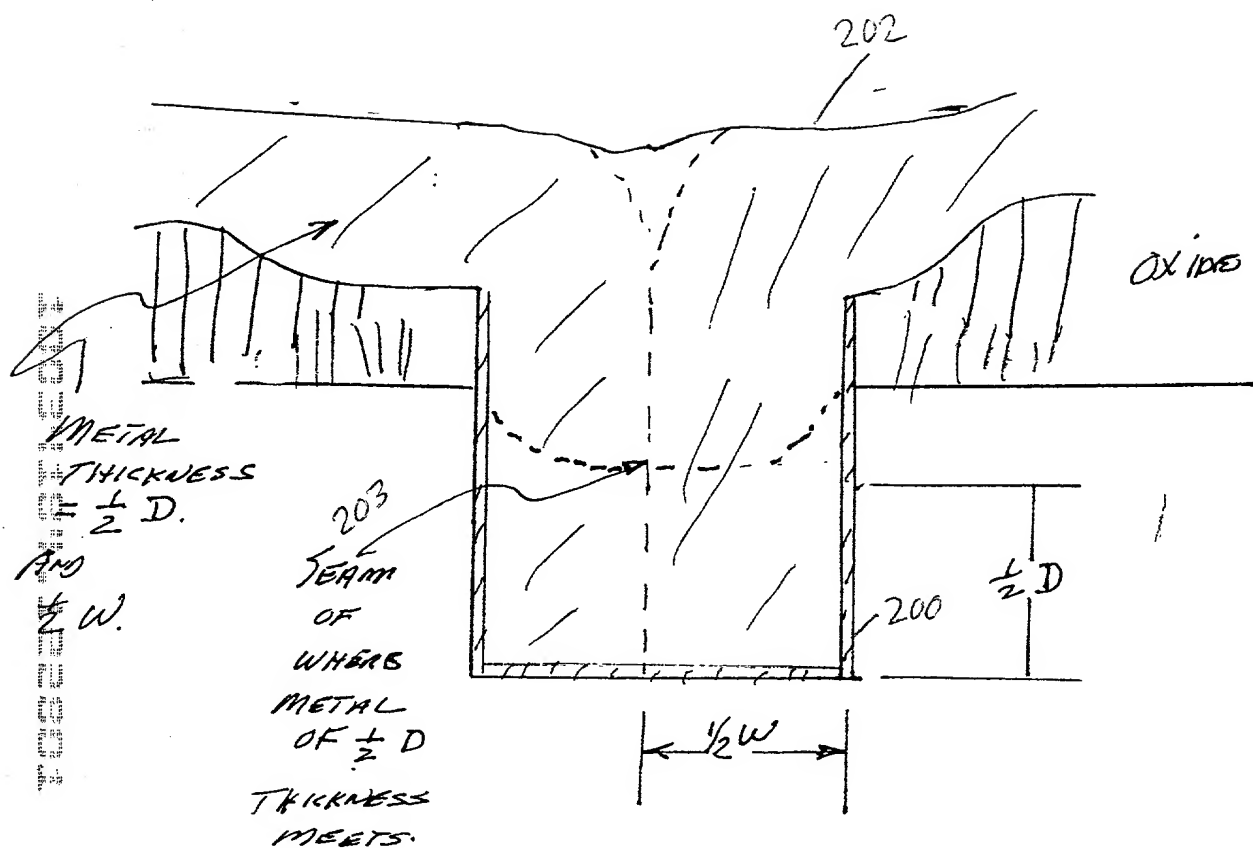
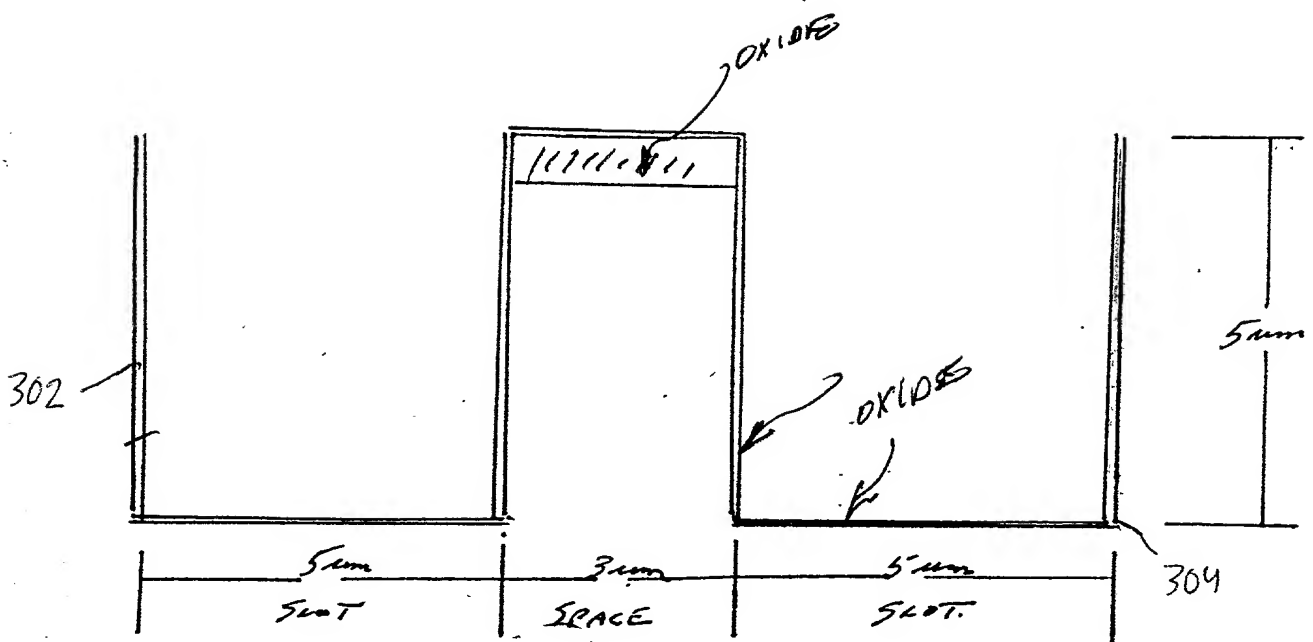
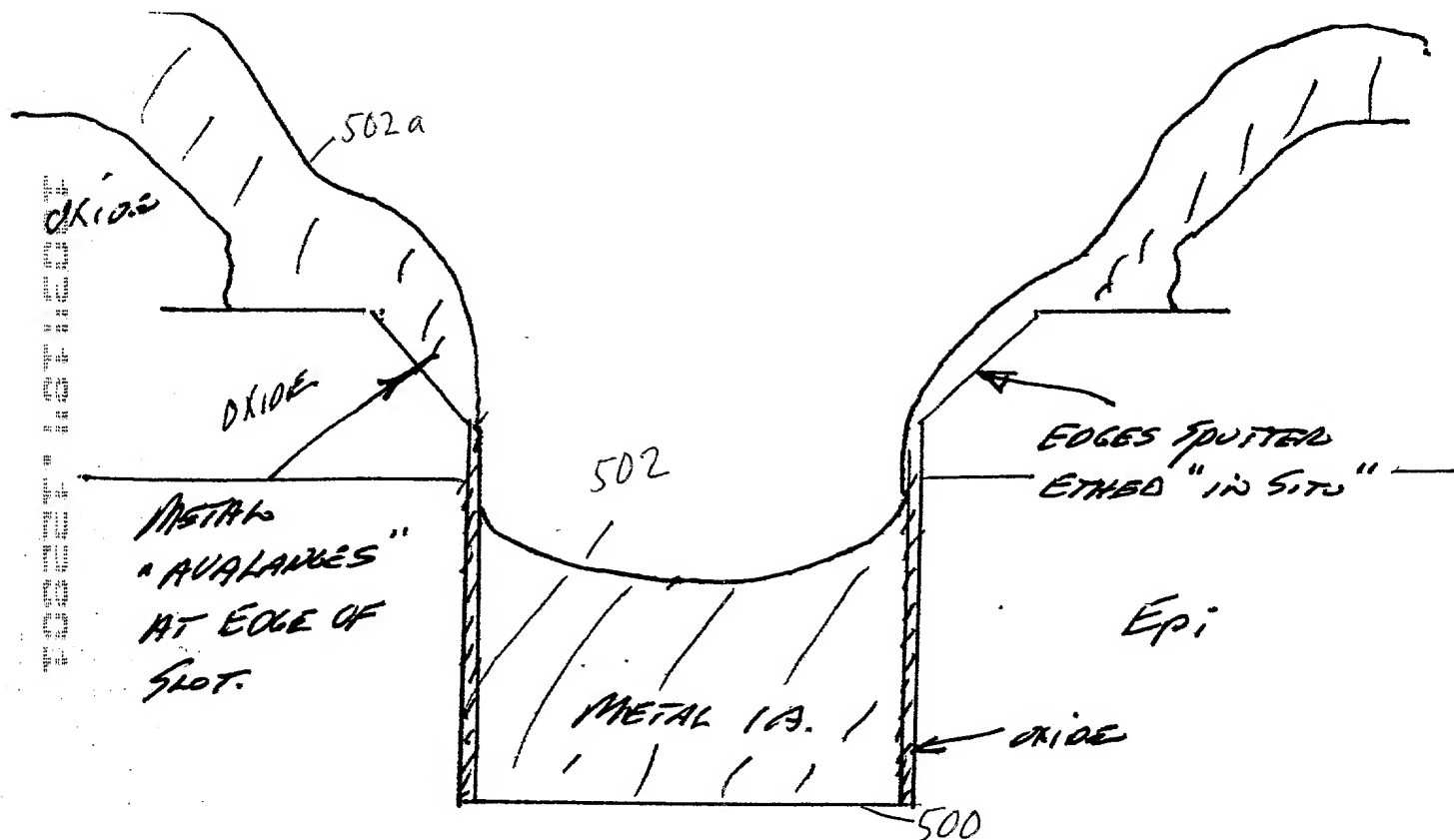


Fig. 4



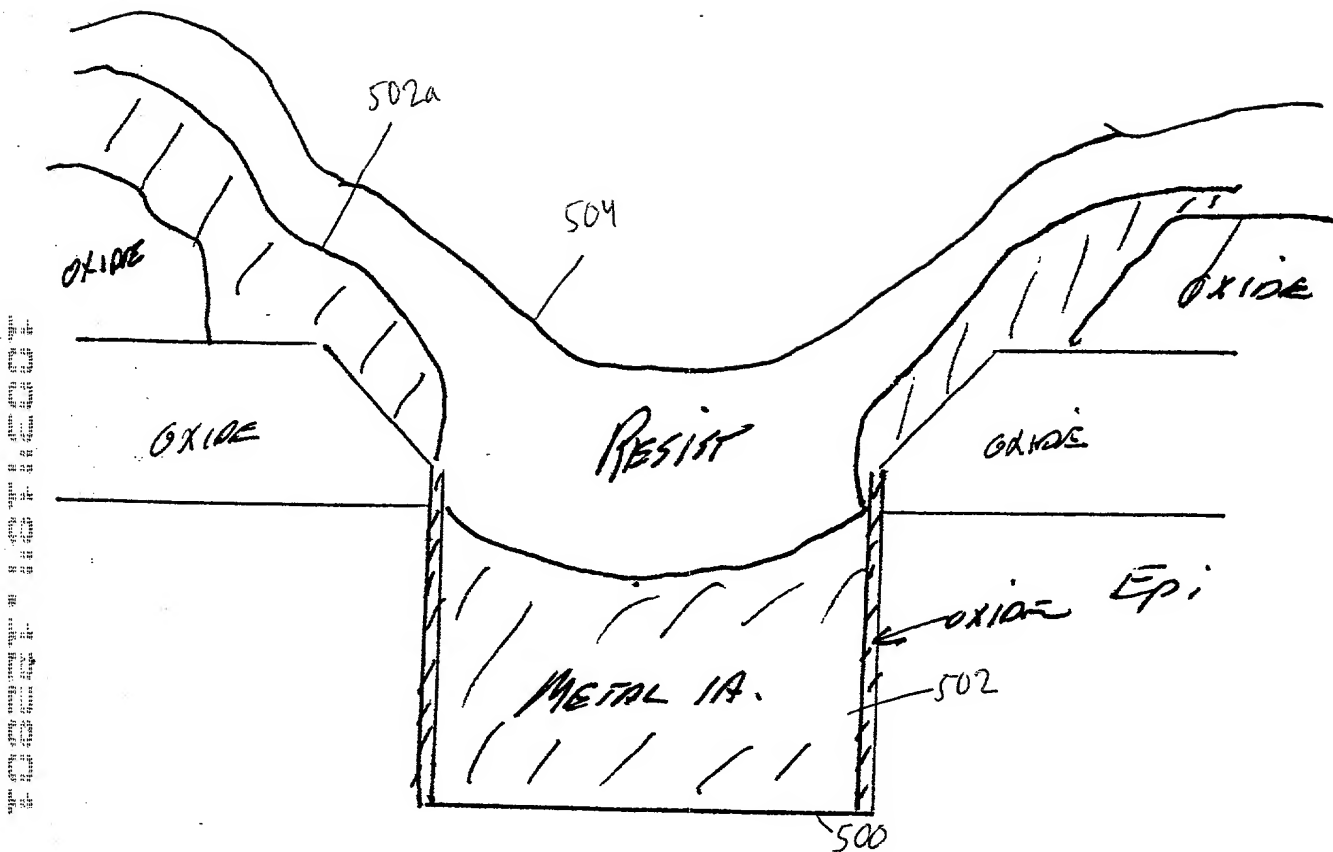
DOUBLE SLOT FOR
DOUBLE WIDTH OF METAL.
3um SPACE BETWEEN SLOTS

Fig. 4a



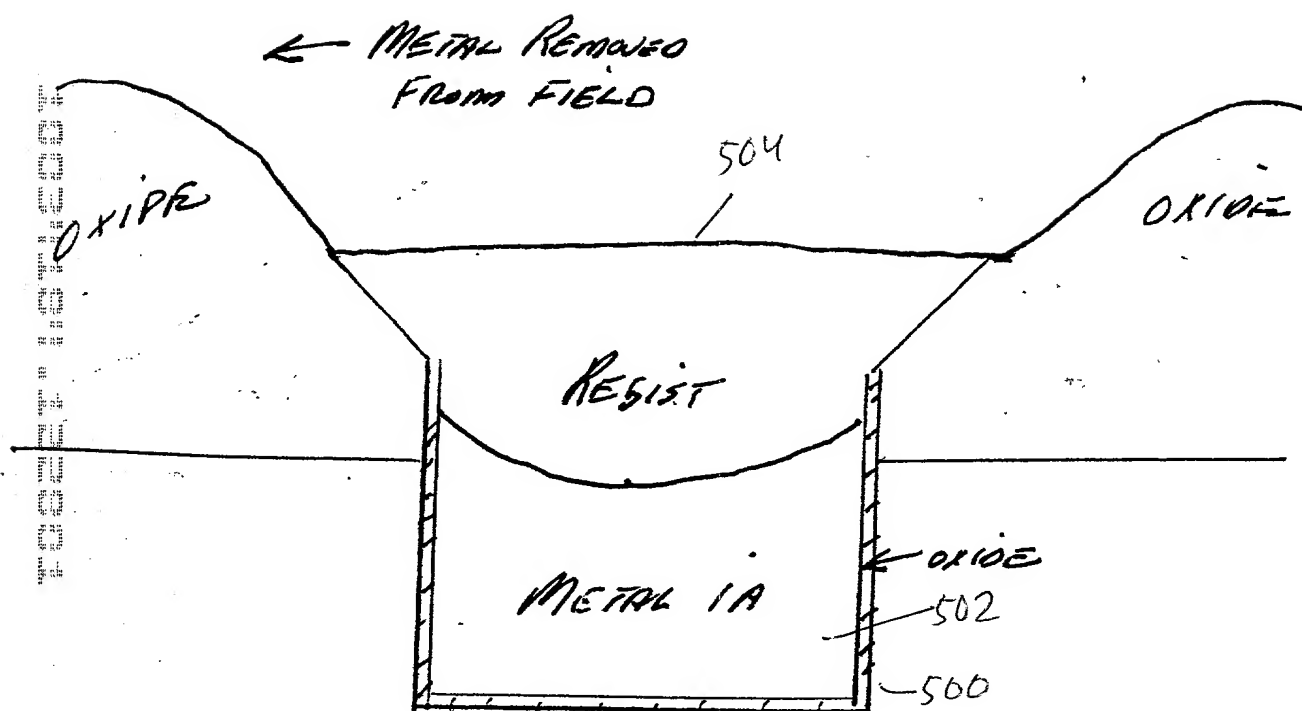
PRIOR TO METAL 1A BEING
 SPUTTERED, THE EDGES OF THE OXIDES
 ARE SPUTTERED ETCHED "IN SITU" &
 1A DEPOSITED

Fig. 5



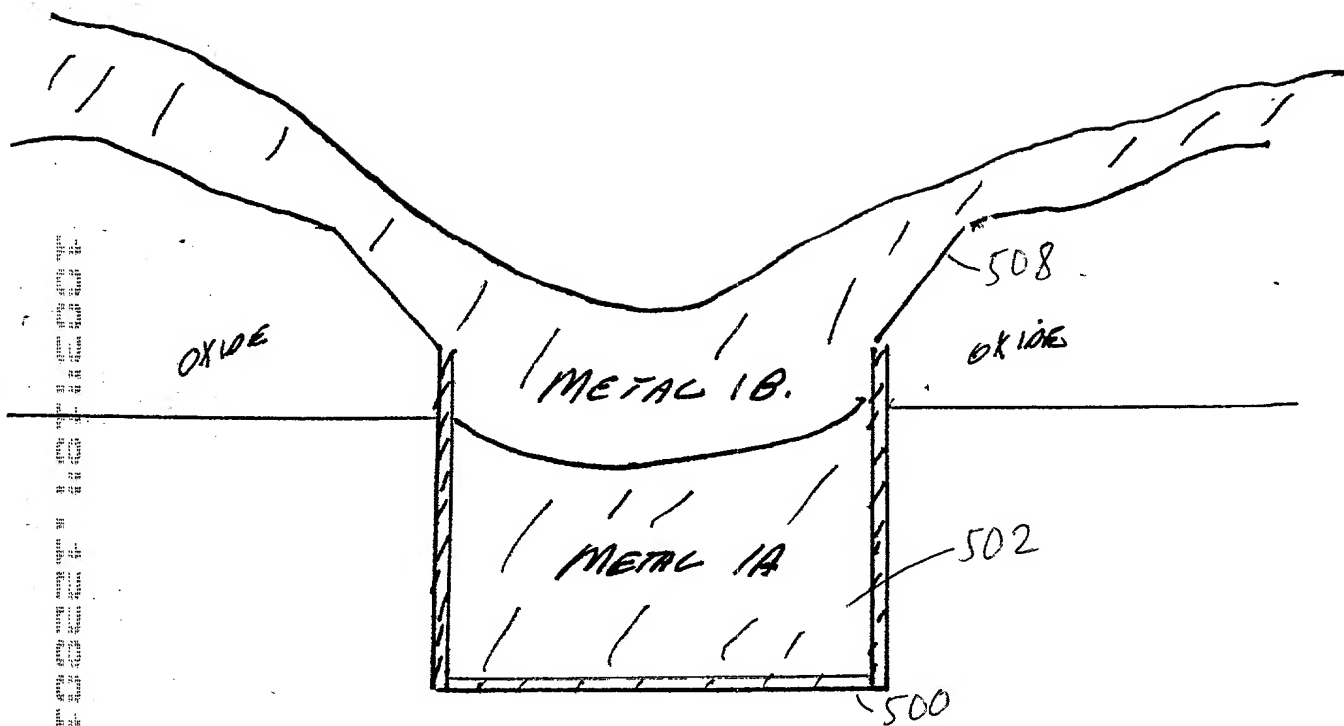
RESIST COATING - THICK IN THE
SLOTS

Fig. 6



RESIST PATTERN ETCHED.
 LEAVING RESIST IN SLOTS.
 FIELD METAL ETCHED OFF.

Fig. 7



RESIST STRIPPED & SECOND
METAL 1B SPUTTER DEPOSITED

Fig. 8

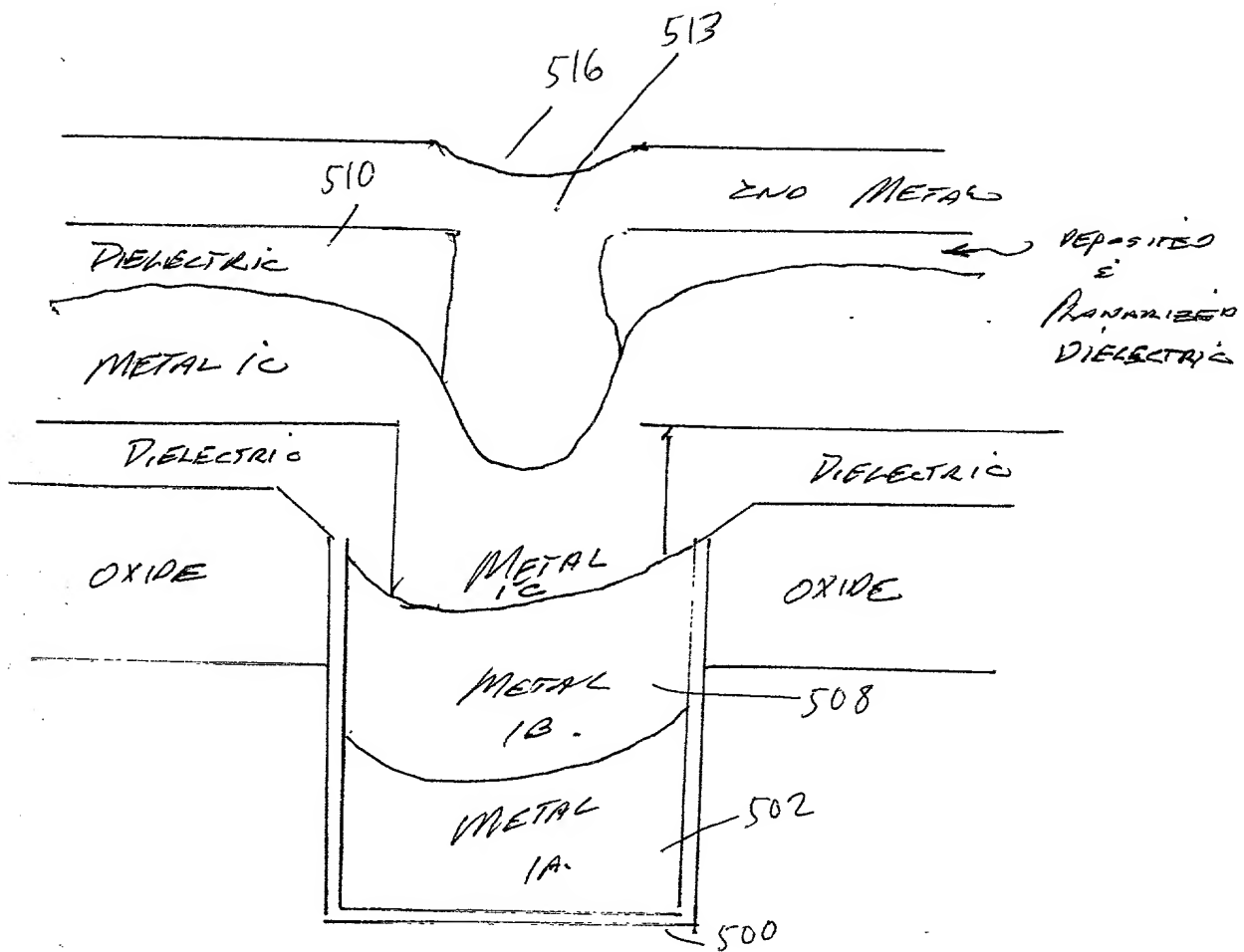
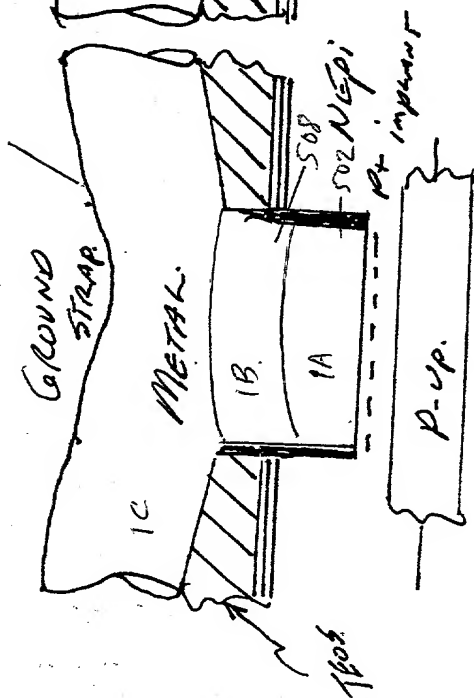


Fig. 10

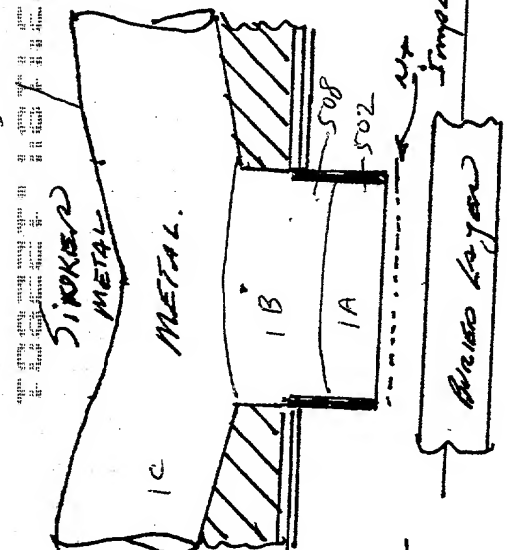
512



604

GROUND STRAP

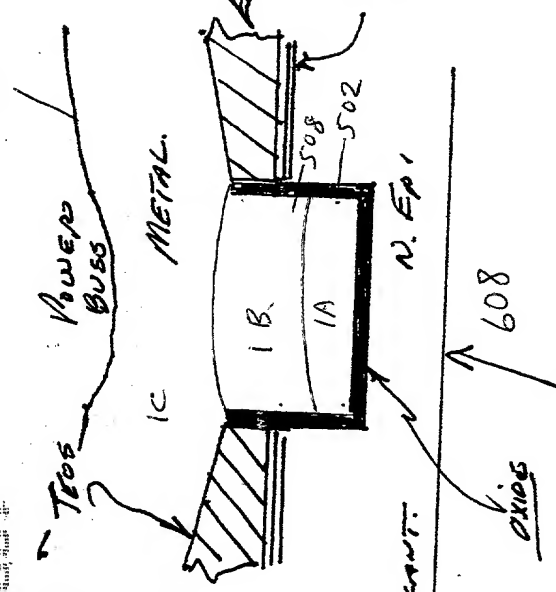
512



606

DRAIN/POWER
Layer / Nt Implant

512



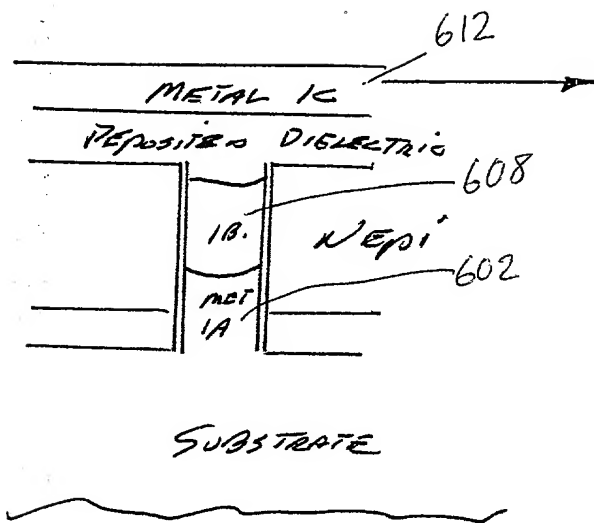
608

POWER BUSS

GROUND STRAP / POWER BUSS / DRAIN METAL SINTER

THIN LAYER OF DIOSCE
FOLLOWED BY 9000 Å TEOS - POLISH -
THIN MASK - METAL.
METAL 15"-20 nm deposited

Fig. 11 POWER METAL.



METAL IC
 CONNECTS AN ISOLATED
 ISLAND TO ADJACENT
 ISOLATED EPI ISLANDS
 AND CROSSES OVER THE
 ISOLATION GROUND
 STRAP BY NOT OPENING
 A VIA IN THIS PORTION
 TO ALLOW IC TO BE
 ISOLATED FROM GROUND.

Fig. 12